Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	2279596	(wafer\$I or semiconductor\$1 or chip\$I or subtrat\$I or IC or intergrated adj circuit or PCB or printed adj circuit adj board)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:02
L2	722743	(etching or chemical adj vapor adj deposition or CVD or metallization adj layers or passivation adj layers or insulation adj layer or photoresist adj stripping or passivation adj polymer adj layer adj removal or lithographic)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:08
L3	627			ON	2006/10/23 09:58	
L4	19	inspecting and visualization adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:22
L5	411182	L1 and L2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:14
L6	456	L5 and L3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:14
L7	0	L4 and L6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:15
L8	456	L5 and L6	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:16
L9	1	L8 and electrostatic adj chuck adj head and adhesive adj tape	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:17

L10	0	L8 and polymer adj coatings same generat\$4 same particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT;	OR	ON	2006/10/23 09:41
L11	0	L8 and polymer adj coatings and generat\$4 and particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:20
L12	0	L1 and polymer adj coatings and generat\$4 and particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:20
L13	0	L5 and polymer adj coatings and generat\$4 and particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:21
L14	0	L3 and polymer adj coatings and generat\$4 and particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:21
L15	0	L3 and polymer adj coatings and generat\$4 adj particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:21
L16	0	polymer adj coatings and generat\$4 adj particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:51
L17	0	inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:41
L18	0	L2 and inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:24
L19	0	L1 and inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:24

L20	0	L8 and(ccd or camera or sensor\$1 or detector)and inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:25
L21	0	(ccd or camera or sensor\$1 or detector)and inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:50
L22	393	L8 and(@ad<"20030608" or @ad<"20030608" or @rlad<"20030608" or @prad<"20030608" or @ptad<"20030608")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:43
L23	0	L22 and motion adj actuating adj mechanism	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:32
L24	1	L22 and motion adj actuating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:43
L25	0	L22 and(ccd or camera or sensor\$1 or detector)and inspecting and visualization adj condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:40
L26	0	L22 and(ccd or camera or sensor\$1 or detector\$1)and inspecting and visualization and condition adj interior and chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:40
L27	0	coatings same generat\$4 same particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:41
L28	0	inspecting and condition and interior adj chamber adj process	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:42
L29	324	inspecting and condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:57

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L30	295	L29 and(@ad<"20030608" or @ad<"20030608" or @rlad<"20030608" or @prad<"20030608" or @ptad<"20030608")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:54
L31	0	L30 and motion adj actuating	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:43
L32	168	L30 and(ccd or camera or sensor\$1 or detector\$1)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:39
L33	0	L32 and polymer near3 coatings and generat\$4 adj particles and disloged adj surfaces and contaminat\$3 adj wafers	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:52
L34	0	L32 and polymer and coatings and generat\$4 and particles and disloged and surfaces adj contaminat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:53
L35	0	L32 and polymer and generat\$4 and particles and disloged and surfaces adj contaminat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:54
L36	0	L32 and polymer and particles and disloged and surfaces adj contaminat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:54
L37	1	L32 and polymer and particles and surfaces adj contaminat\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:54
L38	1	L37 and(@ad<"20030608" or @ad<"20030608" or @rlad<"20030608" or @prad<"20030608" or @ptad<"20030608")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:42
L39	1	L38 and motion	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:57

L40	1	L39 and inspecting and condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:58
L41	1	L40 and L1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:58
L42	1	L41 and L2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:58
L43	0	L42 and(defect or flaw or fault or defective or mechanical adj malfunction or accumulation adj excessive adj levels adj polymer adj deposition)same process adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:01
L44	0	L42 and(defect or flaw or fault or defective or mechanical adj malfunction or accumulation adj excessive or polymer adj deposition) and process adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 09:59
L45	0	L42 and(defect or flaw or fault or defective or mechanical adj malfunction or accumulation adj excessive or polymer adj deposition) and condition adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:00
L46	0	L42 and(defect or flaw or fault or defective or mulfunction or polymer adj deposition)and condition adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:01
L47	0	L42 and(defect or flaw or fault or defective or mulfunction)and condition adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:01
L48	1	L42 and(defect or flaw or fault or defective or mulfunction)and condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:01

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L49	1	L42 and(defect or flaw or fault or defective or mechanical adj malfunction or accumulation adj excessive adj levels adj polymer adj deposition)and condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:02
L50	0	L49 and recording	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:41
L51	0	L49 and record\$3	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:37
L52	0	L49 and(ccd or camera or sensor\$1 or detector\$1)same moving same condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:40
L53	0	L8 and(ccd or camera or sensor\$1 or detector\$1)same moving same condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:41
L54	0	L40 and(ccd or camera or sensor\$1 or detector\$1)same moving same condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:41
L55	4	L5 and(ccd or camera or sensor\$1 or detector\$1)same moving same condition near3 chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:42
L56	0	L55 and recording	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:41
L57	0	L55 and(ccd or camera or sensor\$1 or detector\$1)same recording	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB		ON	2006/10/23 10:42

L58	0	L55 and(ccd or camera or sensor\$1 or detector\$1)and recording	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:42
L59	4	L55 and(@ad<"20030608" or @ad<"20030608" or @rlad<"20030608" or @prad<"20030608" or @ptad<"20030608")	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 10:59
L60	3	L59 and transfer adj chamber	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:11
L61	0	L59 and transfer adj chamber and adjacent near3 positioning	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:01
L62	0	L60 and transfer adj chamber and adjacent near3 positioning	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:01
L63	0	L60 and transfer adj chamber and adjacent and positioning	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:01
L64	1	lin-chien-fang.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:12
L65	20	lin-chung-yuan.in.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:12
L66	1	L65 and L1	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:12
L67	1	L66 and L2	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2006/10/23 11:12

L68	1	L67 and L3	US-PGPUB; USPAT; EPO; JPO; DERWENT;	OR	ON	2006/10/23 11:13
			IBM_TDB			